

US DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICE

APPLICANT: MARTIN RICHARDSON  
FOR: EUV, XUV, AND X-RAY WAVELENGTH SOURCES CREATED FROM LASER PLASMA  
PRODUCED FROM LIQUID METAL SOLUTIONS

LIST OF ART CITED BY APPLICANT

U.S. PATENT DOCUMENTS

EXAMINER	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
AA	4,024,400	05/17/77	Blytas et al.	250	432	05/13/76
AB	4,328,464	05/04/82	Pivrotto	330	4.3	02/07/80
AC	4,700,371	10/13/87	Forsyth et al.	378	34	11/08/84
AD	4,723,262	02/02/88	Noda et al.	378	119	12/26/85
AE	4,866,517	09/12/89	Mochizuke et al.	378	119	09/10/87
AF	4,953,191	08/28/90	Smither et al.	378	143	07/24/89
AG	5,126,755	06/30/92	Sharpe et al.	346	75	03/26/91
AH	5,142,297	08/25/92	Eijkman et al.	346	1.1	03/26/90
AI	5,148,462	09/15/92	Spitsyn et al.	378	143	04/08/91
AJ	5,151,928	09/29/92	Hirose	378	119	08/20/91
AK	5,243,638	09/07/93	Wang et al.	378	119	03/10/92
AL	5,257,303	10/26/93	Das Gupta	378	85	08/03/92
AM	5,459,771	10/17/95	Richardson et al.	378	119	04/01/94
AN	5,577,091	11/19/96	Richardson et al.	378	119	01/13/95
AO	5,577,092	11/19/96	Kublak et al.	378	119	11/19/96
AP	5,991,360	11/23/99	Matsui et al.	378	119	02/03/98
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FOREIGN PATENT DOCUMENTS

FA JP 1A57141167 03/1982  
FB JP 1A0267895 11/90 Iwamatsu

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